

# **Development of Epitaxial Ga<sub>2</sub>O<sub>3</sub> Thin Films for Next Generation Power Electronics**

## **Detailed Topic**

The demand for power electronic devices keeps increasing due to the rapid development of industries related to electricity, automotive and consumer electronics. In order to meet this demand, the use of wide bandgap semiconductors such as diamond, aluminum nitride or gallium oxide (Ga<sub>2</sub>O<sub>3</sub>) has emerged as a potential avenue for development. Among these materials,  $\beta$ -phase Ga<sub>2</sub>O<sub>3</sub> has many advantages, such as an ultra-wide bandgap energy (4.6-4.9 eV), a particularly high breakdown electric field ( $\approx 8$  MV/cm) as well as a decent electron mobility ( $\approx 250$  cm<sup>2</sup>/Vs). In addition, the availability of large and reasonable-cost Ga<sub>2</sub>O<sub>3</sub> substrates makes it possible to consider this semiconductor as building block for next-generation power devices.

The objective of the PhD thesis will consist in developing the growth of epitaxial Ga<sub>2</sub>O<sub>3</sub> thin films by comparing two complementary chemical deposition techniques, namely i) chemical bath deposition using a home-made reactor operating at low temperature and ii) pulsed liquid injection metalorganic chemical vapor deposition using a semi-industrial reactor operating at high temperature. A wide range of morphological and structural characterization techniques will be used, including scanning and transmission electron microscopy, X-ray diffraction, and Raman spectroscopy, to finely assess and optimize the formation mechanisms of thin films involved, their structural quality, as well as the interface properties with the substrate. The optical and electrical properties of Ga<sub>2</sub>O<sub>3</sub> thin films will be further characterized by optical absorption, cathodoluminescence, Fourier Transform infrared spectroscopy, I-V, C-V, deep level transient spectroscopy, and photoconductivity measurements. Finally, the possibility to integrate Ga<sub>2</sub>O<sub>3</sub> thin films into dedicated transistors for power electronics will be considered.

## Location & Duration

The candidate will work in the Materials and Physical Engineering Laboratory (LMGP), in the Nanomaterials and Advanced Heterostructures team (NanoMAT), as well as in Institut Néel, in the Wide Band Gap Semiconductor team (SC2G).

Web sites: http://www.lmgp.grenoble-inp.fr/ and https://neel.cnrs.fr/

### Profile & Required Skills

The applicant should be an Engineering School or Master 2 student in the fields of materials science and engineering and/or semiconductor physics. Specific skills for teamwork and oral and written English expression will be appreciated. We are looking for dynamic and highly motivated candidates.

**PhD Thesis Funding:** The funding is available *via* the Cross-Disciplinary Program project POWER ALPS (2023 – 2026) gathering the community of Grenoble (i.e. UGA, CNRS, CEA, industries...) around power electronics.

### **Contacts**

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